

Supporting Information for:

Robust Spin-on-Glass Poly(methyl)silsesquioxane-based Low- k Materials Derived from a Cyclic Siloxane Precursor

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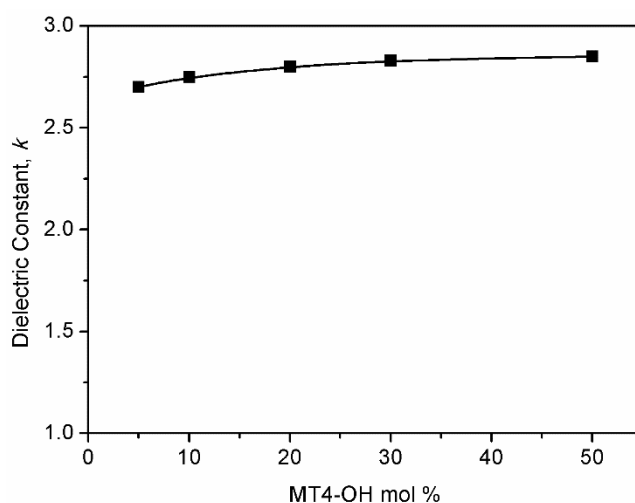


Fig S1. Dielectric constant values for MT4-MSSQ spin-on-glass as-cast resins

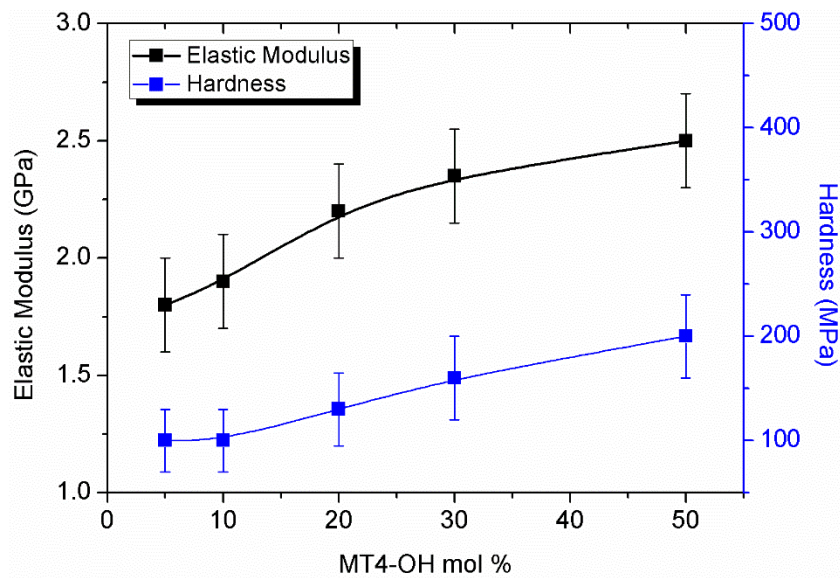


Fig S2. Elastic Moduli and hardness values of various MT4-MSSQ spin-on-glass as-cast resins